

ABSTRACT

There is provided a vacuum vapor processing apparatus which is capable of adjusting the amount of supply of metal atoms to an object to be processed and which has a simple construction. The vacuum vapor processing apparatus is provided with: a vacuum chamber (12) capable of keeping inside thereof at a predetermined pressure; a processing vessel (2) and an evaporating vessel (3), both being disposed in the vacuum chamber at a distance from, and in communication with, each other; and heating means (6a, 6b) capable of heating the processing vessel and the evaporating vessel in a state in which the object to be processed is disposed in the processing vessel (S) and in which metal evaporating material (V) is disposed in the evaporating vessel. The processing vessel and the evaporating vessel are respectively heated by the heating means to thereby evaporate the metal evaporating material while raising the object to be processed to a predetermined temperature so that evaporated metal atoms are supplied to the surface of the object to be processed in the processing vessel.